

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Continuation Application of)	Examiner: not assigned
Nulman, et al.)	
Parent Serial No.: 08/851,946)	Art Unit: not assigned
Parent Filing Date: May 6, 1997)	

For: COILS FOR GENERATING A PLASMA AND FOR SPUTTERING

SECOND PRELIMINARY AMENDMENT

Assistant Commissioner of Patents
Washington, D.C. 20231

Dear Sirs:

After granting a filing date and prior to issuing a first action in the above-referenced continuation application, please enter and consider the following amendments:

IN THE CLAIMS:

Please cancel Claim 1 without prejudice.

Please enter the current claim set as follows:

41. An apparatus for use with a signal source, for sputter deposition of a film layer onto a substrate, comprising:

a vacuum chamber having a substrate support member disposed therein, a plasma generation area within said chamber, and a shield having a wall which substantially encircles said plasma generation area and said substrate support member;

a first biasable target disposed in said chamber;

a capacitor; and

a sputterable coil insulatively carried by said shield wall and having a first end coupled to said signal source and a second end coupled to said capacitor, wherein said coil substantially encircles said plasma generation area and is positioned to couple energy inductively into said plasma generation area and positioned adjacent to said substrate support member to sputter material from said coil onto said substrate.

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